# Study of Non-Linear Optical Properties using Z-Scan

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#### Abstract

In this experiment, we started with learning non linear optics basics and its uses. Then we explored the Single Beam Z-Scan Technique and saw how Z-Scan traces for different materials can be obtained. We have analyzed these traces using Python and saw how the Non-Linear Refractive Index and the Non-Linear Absorption Coefficient, then we calculated it for toulene and acetone. We have also examined certain future directions that we could take this experiment in. We tried to make a optical transistor using non linear refractive index property.

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# 1 Objective

- To study the basics of Non-Linear Optical Properties by using Z-scan Techniques.
- Taking measurements of transmitted power for open and closed aperture by translating the material in the z-direction.
- By fitting these data with the appropriate formulas, we will find the medium's nonlinear absorption coefficient and nonlinear refractive index for Acetone and Toulene.
- In the new idea section, try to make an Optical transistor and explain the things happening there and suggest further improvement in the setup.

#### 2 Overview

The non-linear optical properties of materials have found several applications in recent times, primarily in ultra-fast optical switching and signal processing applications. In such cases, the relevant phenomena are Non-Linear Refraction (NLR) and Non-Linear Absorption (NLA). The

Single Beam Z-Scan technique, is one of the principal techniques to explore these non-linear material characteristics owing to its simplicity and high sensitivity.

This technique can rapidly provide a measure of both NLR and NLA in solids as well as liquids (including solutions), yielding the sign as well as the magnitude of the nonlinear refractive index and the nonlinear absorption coefficient. technique is based on the principles of spatial beam distortion. It makes use of the fact that a spatially transverse variation in LASER intensity induces non-linear optical changes in the material, giving rise to a lens-like effect, which in turn affects the beam propagation. This leads to a self-focusing or defocusing effect (self-lensing effect). This in turn causes changes in the farfield diffraction pattern, that can be utilized to obtain the relevant nonlinear optical properties of materials. "Single Beam", in the name, comes from the fact that a single Gaussian laser beam in a tight focus geometry, is used to induce the non-linear effects.

# 3 Theory

Nonlinear Optics is a branch of optics that deals with light behavior in non-linear media(Polarization P relates non-linearly with electric field).

While considering nonlinear optical materials, two properties of interest are the material's nonlinear refractive index and its nonlinear absorption coefficients. Both change the intensity of light non-linearly when light passes through a medium.

The Z-Scan is based on the principle of spatial beam distortion used to

measure the third-order optical nonlinearity and allows computing the contributions of nonlinear absorption and nonlinear refraction.

#### 3.1 Nonlinear Optical Media

In a linear dielectric medium, there is a linear relation between Electric field and induced electric polarization

$$\mathbf{P} = \epsilon_0 \chi \mathbf{E}$$

where  $\epsilon_0$  is the electric permittivity of vacuum and  $\chi$  is the dielectric susceptibility of the medium. In a nonlinear dielectric medium, **P** and **E** are related non-linearly.

$$\mathbf{P}(\mathbf{E}) = \epsilon_0 \left( \chi^{(1)} \mathbf{E} + \chi^{(2)} \mathbf{E} \mathbf{E} + \chi^{(3)} \mathbf{E} \mathbf{E} \mathbf{E} + \dots \right)$$

where  $\chi^{(n)}$  are the higher order susceptibilities which governs the nonlinear processes. When the intensity of the light will be sufficiently high, only then these higher order polarization terms will be significant.

#### 3.2 Nonlinear wave equation

A wave equation for propagation of light in a nonlinear medium can be derived from maxwell equations

$$\nabla^2 \mathbf{E} - \frac{1}{c^2} \frac{\partial^2 \mathbf{E}}{\partial t^2} = \mu_0 \frac{\partial^2 \mathbf{P}}{\partial t^2}$$

We can write **P** as sum of linear and nonlinear terms separately where  $\mathbf{P}_{NL}$  is  $\mathbf{P}_{NL} = \chi^{(2)}\mathbf{E}\mathbf{E} + \chi^{(3)}\mathbf{E}\mathbf{E}\mathbf{E} + \dots$  equations,  $n^2 = 1 + \chi, c = \frac{1}{n}$  and velocity of light in a Now, by using the equations,  $n^2 = 1 + \chi, c = \frac{1}{n}$  and velocity of light in a medium of refractive index  $n, v = \frac{c}{n}$ , we can write wave equation in a nonlinear medium

$$\nabla^2 \mathbf{E} - \frac{1}{v^2} \frac{\partial^2 \mathbf{E}}{\partial t^2} = \mu_0 \frac{\partial^2 \mathbf{P}_{NL}}{\partial t^2}$$

This is the basic equation in the theory of nonlinear optics.

#### 3.3 Third-order Nonlinear Optics

We generally work with centrosymmetric media (the properties of the medium which are not altered by the transformation  $\mathbf{r} \to -\mathbf{r}$ ). Hence  $\chi^{(2)}, \chi^{(4)}, \chi^{(6)}, \ldots$  terms will vanishes. and hence third order term  $\chi^{(3)}$  becomes more important. Equation (2.2) will become

$$\mathbf{P}(\mathbf{E}) = \epsilon_0 \chi^{(1)} \mathbf{E} + 0 + \epsilon_0 \chi^{(3)} \mathbf{E} \mathbf{E} \mathbf{E}$$

where  $\mathbf{E}$  is

$$\mathbf{E} = \frac{1}{2} \left( E_0 e^{ikz - i\omega t} + E_0^* e^{-ikz + i\omega t} \right)$$

Put this eq. in (2.7), we get

$$\mathbf{P}(\mathbf{E}) = \epsilon_0 \left( \chi^{(1)} + \frac{3}{4} \chi^{(3)} |E_0|^2 \right) \mathbf{E}$$

Hence  $\chi_{eff} = \chi^{(1)} + \frac{3}{4}\chi^{(3)} |E_0|^2$ . We have relation between refractive index n and susceptibility  $\chi_{eff}$ 

$$n^{2} = 1 + \chi_{\text{eff}} = 1 + \chi^{(1)} + \frac{3}{4}\chi^{(3)} |E_{0}|^{2}$$
$$n^{2} = n_{0}^{2} + \frac{3}{4}\chi^{(3)} |E_{0}|^{2} = n_{0}^{2} \left(1 + \frac{3\chi^{(3)} |E_{0}|^{2}}{4n_{0}^{2}}\right)$$

where we have used  $n_0^2 = 1 + \chi_0$  (where  $n_0$  is the linear component of refractive index). Now take square root both side and use binomial expansion, we get

$$n = n_0 \left( 1 + \frac{3}{8n_0^2} \chi^{(3)} |E_0|^2 \right) = n_0 + \frac{3}{8n_0} \chi^{(3)} |E_0|^2$$

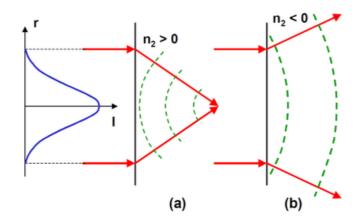
By using relation  $I = \frac{1}{2}\epsilon_0 n_0 c |E_0|^2$ 

$$n = n_0 + \frac{3}{4}\chi^{(3)} \left(\frac{I}{\epsilon_0 n_0^2 c}\right)$$
$$n = n_0 + n_2 I$$

where  $n_2 = \frac{3\chi^{(3)}}{4\epsilon_0 n_0^2 c}$  is a nonlinear component of the refractive index. And hence we can increase the nonlinear effects by increasing the intensity of incident light. This effect is known as Optical Kerr effect, i.e. change of refractive index of a material in response to an applied electric field.

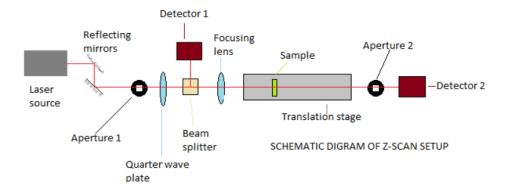
#### 3.3.1 Self-focusing and defocusing

Self-focusing and defocusing is a non-linear optical processes induced by the change in refractive index of materials exposed to intense electromagnetic radiation. A medium whose refractive index increases with the electric field intensity acts as a focusing lens(fig a) for a Gaussian beam, while if it decreases with electric field intensity acts as defocusing lens(fig b).

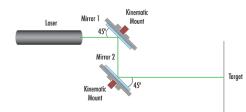


## 4 Z-Scan Experimental setup

#### 4.1 Apparatus used and their Working



- Laser Source: We use the pulsed 532 nm laser.
- We used the two reflecting mirrors for aligning the beam by Parallel (Z-Fold) Configuration(as shown in below figure)



- Wave plate: Optical device which alter the polarization state of light wave traveling through it. There are two types of wave plate, first half wave plate which shift the polarization direction of linearly polarized light, second is quarter wave plate which converts linearly polarized light into circularly polarized light.
- Beam Splitter: Optical components used to split incident

light at a designated ratio into two separate beams. There will be semi reflective coating on one of the prism. Ratio of reflection/transmission depends on coating material. There are two type of beamsplitter, first is polarizing beam splitter(divides incident unpolarized light into orthogonal polarized beams) and second is Non-polarized beam splitter(split by specific percentage that is independent of polarization).

- Note: We are using a combination of wave plate and beamsplitter to control the intensity of laser beam. Through half-waveplate we will bring a polarisation in the light and our beam splitter will split the beam intensity (will reflect some and pass some) as per polarisation.
- Thermal detectors: It is based on temperature change of the

element through the absorption of EM radiation. Change in temperature causes change in temperature dependent property (resistance) of thermal detector, which is evaluated electrically and is measure of the absorbed energy.

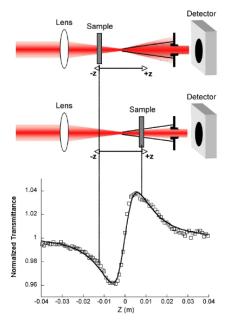
- A Converging Lens (L0), with f = 15 cm, to focus the LASER light.
- A Translation Stage (TS) with wires and con- trol software. It has a stepper motor, which can

run at up to 300 RPM. The end-to-end length covered by the translation stage, with the mounted sample, is 12.2 cm (12400 steps).

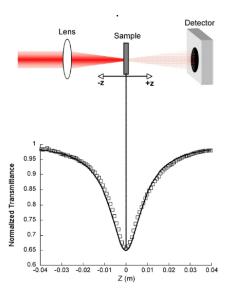
- A Beam Profiler to measure the Beam Waist.
- An Optical Table to assemble the setup.
- Allen Keys and bolts to hold the equipment in place.
- Multiple screens to avoid interference from other setups.

#### 4.2 Principle

When a high intensity laser beam propagates through a material, induced refractive index changes leads to self-focusing or defocusing of the laser beam which enables to determine the third-order nonlinear optical properties of various materials. In this technique, the sample is translated along z direction through the beam waist of a focused beam by keeping the input power of beam constant. In our experiments a continuous pulse wave laser operating at 532 nm was used. The laser beam was focused using a 10 cm focal length lens. Let us consider a material with positive non-linear refractive index,  $n_2 > 0$ . As shown in Fig. 1a), on the side of focus where the beam is converging, the non-linear lens shortens the beam's waist position to a negative z value. As the beam passes through the shifted focus, it diverges at a greater diffraction angle, so the beam's power is spread over a wider area and the intensity of beam passing through the pinhole decreases. When the sample is on the positive z side, where the beam is diverging, the non-linear lens reduces the beam's angle of divergence, thereby increasing the power passing through the pinhole. The effects are exactly opposite for  $n_2 < 0$ .

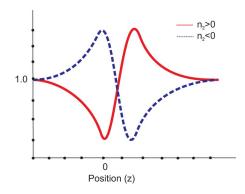


Non-Linear Refraction



Non-Linear Absorption

If the material has a positive non linearity  $(n_2 > 0)$ , the transmittance graph has a valley first and then a peak. For the sample with  $n_2 < 0$  the graph is exactly the opposite (first peak and then valley).



Determination of a sign of  $n_2$  from transmittance graph

The aperture plays an important role in determining which values we are going to find. We use closed aperture for finding out the non-linear refractive index and open aperture to find the absorption coefficient.

# 4.3 Formulas to derive Nonlinear refraction and nonlinear absorption

Consider a Gaussian Beam, propagating along the z-direction with beam waist,  $w_0$ , wavelength,  $\lambda$ , and Rayleigh Length,  $z_0 = \pi w_0^2/\lambda$ :

$$E(r,z) = E_0(t) \frac{w_0}{w(z)} \exp\left(-\frac{r^2}{w(z)^2}\right) \exp\left(-ikz - ik\frac{r^2}{2R(z)}\right) \exp(-i\phi(z,t))$$
(1)

Here,  $k=2\pi/\lambda$  is the Wave Number;  $w(z)=w_0\left(1+x^2\right)$  represents the Beam Width, with  $x=z/z_0$ ; and  $R(z)=z\left(1+x^2\right)$  denotes the Radius of Curvature. The last term,  $\exp(-i\phi(z,t))$ , contains all the radially uniform phase variations. As we only wish to obtain the radial phase variations,  $\Delta\phi(r)$ , we can apply the Slowly Varying Envelope Approximation (SVEA) and ignore phase changes that are uniform in r. Now, let this beam be transmitted through a Kerr non-linear optical material of length, L. Then, considering a centrosymmetric medium, we can write the refractive index and absorption coefficient as:

$$n(I) = n_0 + n_2 I, (2)$$

$$\alpha(I) = \alpha_0 + \beta I \tag{3}$$

where,  $n_0$  is the linear refractive index, while  $n_2$  denotes the non-linear refractive index and  $\alpha_0$  is the linear absorption coefficient, while  $\beta$  represents the non-linear absorption coefficient. I denotes the intensity of light. For a thin sample, the output field can be written as follows:

$$E_{\text{out}} = E(r, z)e^{-\frac{\alpha_0 L}{2}}(1+q)^{-\frac{ikn_2}{\beta}-\frac{1}{2}}$$
 (4)

where,  $q = \beta I L_{eff}$  with  $L_{eff} = (1 - e^{-\alpha_0 L})/\alpha_0$ , and  $I_0 = |E_0|^2$  is the on-axis intensity at beam waist. For very thin samples, such as in this experiment, we can take  $L_{eff} \approx 1$  (in proper units). Moreover,  $I_0$  can be written as:

$$I_0 = \frac{P_{Avg}}{RR \times PW \times (\pi w_0^2)},\tag{5}$$

where,  $P_{Avg}$  is the average beam power, RR is the LASER Repetition Rate, PW is the LASER Pulse Width and  $\pi w_0^2$  is the beam area, at focus.

The intensity distribution and phase shift of the beam, at the exiting surface, must also fulfill these criteria [2]:

$$I_{\text{out}}(r,z) = I(r,z) \frac{\exp(-\alpha_0 L)}{1 + q(r,z)}$$
 (6)

and,

$$\Delta \phi = \frac{kn_2}{\beta} \ln(1 + q(r, z)) \tag{7}$$

Now, the intensity, I(r, z), can be expressed as the product of  $I_0$  and a local Gaussian profile,  $G_{local}$  [2], that can be written as follows:

$$G_{local} = \frac{1}{1+x^2} \exp\left(-\frac{2r^2}{w^2(z)}\right) \tag{8}$$

When only NLR is present, we can write the non-linear phase change as:

$$\Delta \phi = \Delta \Phi_0 G_{\text{local}} \tag{9}$$

while for materials exhibiting pure NLA, q takes the following form:

$$q(r) = \Delta \Psi_0 G_{\text{local}} \tag{10}$$

Here,  $\Delta\Phi_0$  and  $\Delta\Psi_0$  are merely the results of the respective first order expansions of the expressions for  $\Delta\phi$  (Eq. 7) and q, in the cases of pure NLR and pure NLA respectively. This gives us:

$$\Delta\Phi_0 = kn_2 I_0 L_{eff} \tag{11}$$

and,

$$\Delta\Psi_0 = 2^{-1.5}\beta I_0 L_{eff} \tag{12}$$

Substituting these quantities from Eq. 9 and Eq. 10 into Eq. 4, we obtain a final expression for the outgoing field:

$$E_{\text{out}} = E(r, z)e^{-\frac{\alpha_0 L}{2}} \left(1 + \Delta \Psi_0 G_{\text{local}}\right)^{-\frac{i\Delta\Phi_0}{\Delta\psi_0} - \frac{1}{2}}$$
(13)

Now, making use of SVEA and the Gaussian Decomposition method for local field changes and considering only the first two terms in the decomposition, we can obtain an analytical expression for the complex, on-axis far-field given as ([1], [2]):

$$E_{\text{out}} = E(r, z) \exp\left(-\frac{\alpha_0 L}{2}\right) \sum_{n=0}^{\infty} \left[ \frac{\left[-i\Delta\phi_0(z)\right]^n}{n!} \prod_{n'=0}^n \left(1 - i\left(2n' - 1\right) \frac{\Delta\Psi_0}{\Delta\Phi_0}\right) \right] \exp\left(\frac{-2nr^2}{w^2(z)}\right). \tag{14}$$

Using Eq. 14 we can write the complex field at the aperture planes as follows:

$$E_{a} = E(r, z) \sum_{n=0}^{\infty} \frac{\left[-i\Delta\phi_{0}(z)\right]^{n}}{n!} \prod_{n'=0}^{n} \left(1 - i(2n - 1)\frac{\Delta\Psi_{0}}{\Delta\Phi_{0}}\right) \frac{w_{n0}}{w_{n}} \exp\left(-\frac{r^{2}}{w_{n}^{2}} - \frac{ikr^{2}}{2R_{n}} + i\theta_{n}\right)$$
(15)

Here,  $\Delta \phi_0 = \Delta \Phi_0 / (1 + x^2)$ 

When only NLR is considered,  $\Delta \Psi_0 \rightarrow 0$ , and we can reduce the previous equation to obtain:

$$E_a = E(r, z) \sum_{n=0}^{\infty} \frac{[-i\Delta\phi_0(z)]^n}{n!} \frac{w_{n0}}{w_n} \exp\left(-\frac{r^2}{w_n^2} - \frac{ikr^2}{2R_n} + i\theta_n\right)$$
(16)

Taking d to be the propagation distance in free space, between the sample and the aperture, and g = 1 + d/R(z), we can represent the parameters in Eq. 15 and 16 as follows:

$$\begin{split} w_{n0}^2 &= \frac{w^2(z)}{2n+1} \\ d_n &= \frac{kw_{n0}^2}{2} \\ w_n^2 &= w_{n0}^2 \left(g^2 + \frac{d^2}{d_n^2}\right) \\ R_n^2 &= d\left(1 - \frac{g}{g^2 + d^2/d_n^2}\right)^{-1} \end{split}$$

and,

$$\theta_n = \tan^{-1} \left( \frac{d}{gd_n} \right)$$

The total transmitted power through the aperture can then be obtained by spatially integrating  $E_a(r,t)$ , like so:

$$P_T(\Delta\Phi_0(t)) = \int_0^{r_a} |E_a(r,t)|^2 r \, dr$$
 (17)

This directly yields the normalized Z-Scan transmittance, T(z), using the following expression:

$$T(z) = \frac{\int_{-\infty}^{\infty} P_T \left( \Delta \Phi_0(t) \right) dt}{S \int_{-\infty}^{\infty} P_i(t) dt}$$
 (18)

where  $P_i(t) = \pi w_0^2 I_0(t)/2$  is the instantaneous input power, within the sample, and  $S = 1 - \exp\left(-2r_a^2/w_a^2\right)$ , where subscript - a denotes "aperture". This is where the aperture-dependence of the Z-Scan traces comes in. For closed aperture traces, we can take  $S \approx 0$  and for open aperture traces,  $S \approx 1$ . Now, the normalized transmittance for the on-axis electric field, at the aperture plane, can be written as:

$$T_2(z, \Delta\phi_0) = \frac{|E(r = 0, z, \Delta\phi_0)|^2}{|E(r = 0, z, \Delta\phi_0 = 0)|^2}$$
(19)

On substituting the expression for the field into Eq. 19 and simplifying, we obtain the final expression for T(z),

that considers the effect of both NLR and NLA, as given below:

$$T_2(z, \Delta\Phi_0, \Delta\Psi_0) = 1 + \frac{4\Delta\Phi_0 x}{(x^2 + 9)(x^2 + 1)} - \frac{\Delta\Psi_0}{x^2 + 1}$$
(20)

Eq. 20 provides a two-parameter fitting function for any third-order Z-Scan trace, the two parameters being  $\Delta\Phi_0$  and  $\Delta\Psi_0$ , and we have used it to fit the closed aperture traces, in order to obtain the  $n_2$  values in this experiment. On the other hand, for  $\beta$  values, we take the open aperture traces, that de-emphasize  $\Delta\Phi_0$  or small intensity variations, as the entire signal is being measured. So, we can provide a simpler, one-parameter expression for T(z) in this case:

$$T_2(z, \Delta\Phi_0 = 0, \Delta\Psi_0) = 1 - \frac{\Delta\Psi_0}{r^2 + 1}$$
 (21)

Equations 20 and 21 are the working formulae for this experiment. Figure 4 shows variations in transmittance in Z-scan traces for materials exhibiting pure NLR, pure NLA and both NLR and NLA (mixed case), using various values for  $\Delta\Phi_0$  and  $\Delta\Psi_0$ . It is clear from the plots that NLA suppresses peaks in the mixed Z-Scan traces, as compared to the pure NLR case. This also means that the symmetric nature of pure NLR curves is usually absent in most Z-Scan traces, where both NLR and NLA contribute. As such, we can utilize another interesting quantity, that is the Peak-Valley Transmittance Change,  $\Delta T_{p-v}$ . It is expressed as follows in the closed aperture case (where we shall be using the two-parameter fitting function in Eq. 20):

$$\Delta T_{p-v} = 0.406 \Delta \Phi_0 \tag{22}$$

This relation for  $\Delta T_{p-v}$  should hold even for highly skewed Z-Scan traces. Therefore, it provides us with an excellent tool to verify the quality of our traces.

# 5 Z-Scan Experiment

#### 5.1 Toluene

Specification of the Experimental setup.

- $\bullet$  Effective length of the sample,  $\mathcal{L}_{eff}=1~\mathrm{mm}$
- Repetition rate of Laser = 80kHz
- Pulse width at a given repetition rate = 1.75 ns
- Beam waist of a laser beam =  $35 \times 10^{-6}$  m

#### 5.1.1 Observation And Results

Open Aperture

- RPM of motor = 300
- PowerAverage = 82.07mW
- Non-linear absorption coefficient,  $\beta = (1.307 \pm 0.0814) \times 10^{-8} \text{ mW}^{-1}$

Close Aperture

- RPM of motor = 300
- PowerAverage = 23.11mW
- Non-linear refractive index, n<sub>2</sub> =  $-(2.711 \pm 0.0941) \times 10^{-15} \text{ m}^2 W^{-1}$

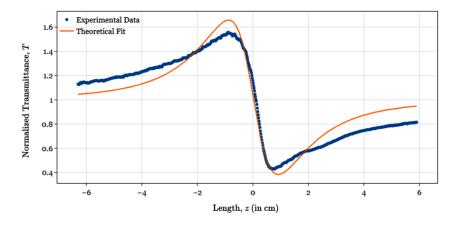


Figure 1: Closed aperature

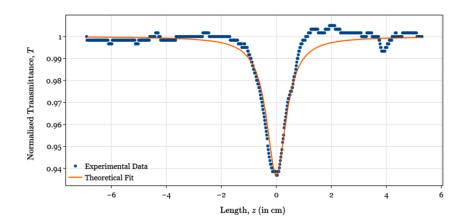


Figure 2: Open aperture

#### 5.2 Acetone

Specification of the Experimental setup.

- Effective length of the sample,  $L_{eff} = 1 \text{ mm}$
- Repetition rate of Laser = 80kHz
- Pulse width at a given repetition rate = 1.75 ns
- $\bullet$  Beam waist of a laser beam =  $35\times 10^{-6}~\text{m}$

#### 5.2.1 Observation And Results

Open Aperture

- RPM of motor = 300
- Average power = 185.7 mW
- Non-linear absorption coefficient,  $\beta = (1.052 \pm 0.0432) \times 10^{-8} \text{ mW}^{-1}$

Close Aperture

- RPM of motor = 300
- Average power = 24.22 mW
- Non-linear refractive index, n<sub>2</sub> =  $-(2.752 \pm 0.6822) \times 10^{-14} \text{ m}^2 W^{-1}$

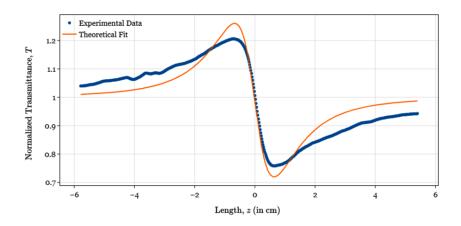


Figure 3: Closed aperature

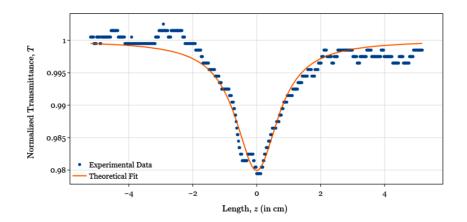


Figure 4: Open aperture

#### 6 Conclusion

We can use Z-scan experimental configuration to obtain nonlinear refractive index and nonlinear absorption coefficients of any standard samples. The sign and magnitude of nonlinear refractive index of the samples can measured. We will then use the equations of normalized transmittance and fit them with the data points and will report the refractive index and nonlinear absorption coefficients. The property of nonlinear sample to change refractive index on changing intensity can be used to make a optical transistor type of thing.

# 7 Improvement and New ideas on the Setup

We want to make an optical transistor. In other words, we want to control the intensity of one laser by changing the intensity of another laser. To get it, we planned to use the nonlinear property of the material. So we made different setups to achieve our goals.

In our first set up we plan to combine Z scan and Michaelson Morley setup. To see whether it is possible to see the change in the refractive index through another laser beam.

# 7.1 Setup 1 and Explanation

We plan to combine Z scan and Michaelson Morley (MM) setup in our first set up. Here, we made the laser from one arm of the MM Setup to pass through the same place of the sample where the laser from the Z Scan arm was already hitting. By changing the intensity of Z-scan arm, we can change the refractive index of the medium(Sample), and since one arm of the MM Setup laser is also falling at the same place of the sample, it will also face some path length change. Our goal was here to see the change in the fringe pattern of the interferometer by changing the intensity of the Z Scan arm laser. Before we could complete the setup and alignment of our first setup, we saw something interesting, which made us go for Setup-2.

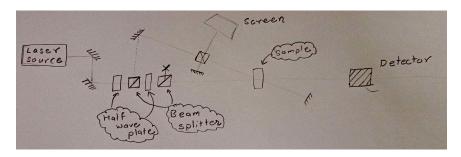


Figure 5: Setup-1

#### 7.2 Setup 2 and Explanation

When we were doing Setup 1, then we observe a black spot in the MM setup's arm which is falling in the Screen (marked in the Setup 2). From now we will call the arm of MM as **Probe Beam** and Z-scan arm as **Push beam**. Here our push beam is focused and probe beam is not.

In the explanation of this black dot formation, we believe that our push beam which is focused is forming a strong lens kind of thing in the Centre of the sample. Here we are keeping the intensity of our push beam higher than the intensity of the probe beam. Now when our unfocused low-intensity probe beam falls on the sample (where a strong lens kind of thing is formed due to push beam) then some part of the probe beam which is directly falling on the lens we call it **Inner probe beam** and the rest is called the **outer probe beam**. Light of inner probe beam hits that area of the sample, where lens effect is strong, the inner beam gets conversed and diverse as we move further away from focus in direction of the probe beam. So the intensity of the inner beam will spread to a large area. But the area on the screen where the inner beam would have hit when there was no sample is having light coming from only the inner beam also when the sample is there. This time, since it is defocused, the light intensity is very low in the central area.

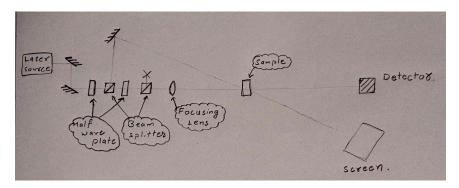


Figure 6: Setup-2

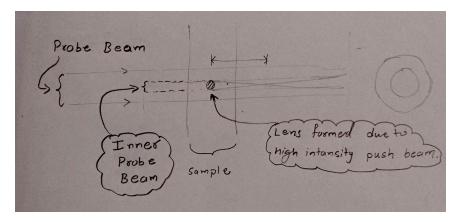


Figure 7: Focusing of Inner probe beam

The intresting thing about this black spot is that it disappears when we stop push beam form passing through sample. This is giving us an opportunity to build the optical transistor using this phenomena.

So for making an optical transistor, we first blocked the light using an aperture in such a way that only the black dot area is having some intensity on the screen and only get the light of the probe beam, which is changing while changing the intensity of the push beam. We want our optical transistor to pass higher information from push beam to probe beam.

When we were varying the push beam intensity from 0 to 156mW, we were getting the blocked probe beam intensity to be changing from 38mW to 2mW. This difference is significant to be measured. For making the difference more visible we planned to make new setup.

#### 7.3 Setup 3 and Explanation

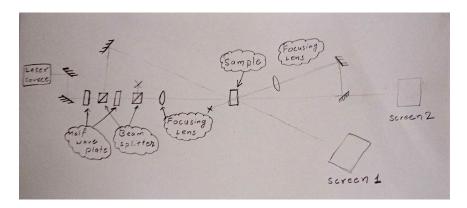


Figure 8: Setup-3

So in this setup, we made our push beam fall on our sample twice by using mirror arrangements and get some significant improvements. When we varied the push beam intensity from 0 to 156 mW, we saw a change in our probe beam intensity from 55 to 2 mW.

#### 7.4 Setup 4 and Explanation

Our sample has a positive  $n_2$  value, so the light passing through the sample will move toward higher intensity. We used this to make the black hole bigger and converge the Gaussian beam to have more intensity in the center. Then we used the two apeture to make the effect of intensity difference higher. When we were varying the intensity of our push beam from 0 to 80mW, we observed a change in our probe beam intensity from 67mW to 3mW, which is better than all the previous setups.

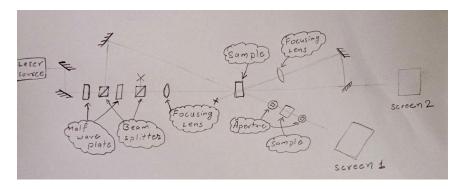


Figure 9: Setup-4

#### 8 Photos and Results

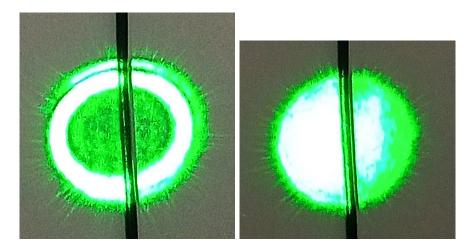


Figure 10: With Push beam on and then Stopped in Setup-3

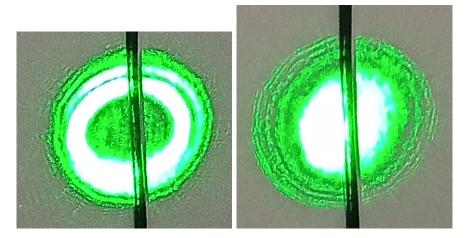


Figure 11: With Push beam on and then Stopped in Setup-4

In Figure 10 from setup- 3, here we are not having that extra sample.we are getting a black spot in the probe beam when push beam is on, and when we stop the push beam then the black spot is filled with a bright light. In Figure 11 from setup-4, here we are having that extra sample.When the push beam is on, we get the dard black spot in the probe light, this time the dark spot is more darker and smaller. When we stop the push beam and see the probe beam then in place of dark spot we get a more brighter light in comparison with the Figure 3.This shows that the setup-4 is better and is really an improvement of setup-3 in order to make a better optical transister.

# 9 Advantages and Disadvantages of Z-Scan

#### Advantages

- It is simple and very sensitive technique to measure the sign and magnitude of nonlinear refraction and absorption coefficients.
- It has no difficult alignment other than beam aligning on the aperture.
- Data analysis is quick and simple.
- It can determine both real and imaginary parts of  $\chi^{(3)}$ .
- Z-scan can also be modified to study non-linearities of higher order contributions.

#### Disadvantages

• It requires a high quality Gaussian  $TEM_{00}$  beam for absolute measurements.

- The analysis must be different if the beam is non-Gaussian.
- Sample distortions, tilting of sample during translation, can cause the beam to walk off the far field aperture.

#### 10 Precautions and Sources of Error

- The polariser should be used to reduce the power of the laser in order to reduce the thermal effects of laser on the samples.
- Protective glasses must be worn while taking measurements and the laser beam shouldn't allowed to fall outside here and there by carefully blocking it with black aluminium plate.
- The lasers should be turned off when not in use.

### 11 References

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